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ABSTRACT

SUBSTRATE PROCESSING APPARATUS AND SUBSTRATE PROCESSING METHOD.

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A substrate processing apparatus is disclosed, comprising:

a temperature regulating section for regulating the temperature of a substrate at a predetermined temperature;

10 a temperature regulation and transfer mechanism for regulating the temperature of the substrate at a predetermined temperature and transferring the substrate;

a main transfer section for receiving and sending the substrate from/to said temperature regulating section and said temperature regulation and transfer mechanism; and

a solution supplying section for supplying a predetermined solution to the substrate,

15 wherein said main transfer section receives and sends the substrate from/to said solution supplying section.

Fig. 1